

Laurell EDC *HL*

The Right Choice for Efficient,
Repeatable, and Safe Processing



Wireless Control through a touchscreen tablet
A streamlined housing with a smaller footprint

Efficient

More successful results using
less chemistry and less DI water,
producing less waste

Repeatable

Easy, accurate controls,
always fresh chemistry,
dry-in dry-out processing

Safe

Independently tested to
international standards



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Complete Solutions

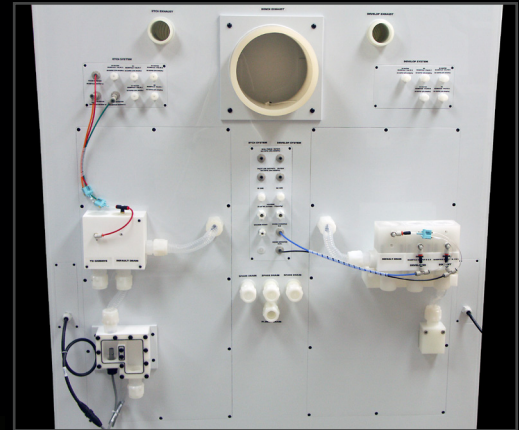
For Your Etch, Develop, or Cleaning Process



Everything you need in one station

Chemical containment and delivery, exhaust provision and control, safe and efficient waste handling—it can all be contained or controlled in a custom-built Laurell Technologies wet station

Compact two-foot single-processor stations and flexible four-foot dual-processor options simplify installation and operation with “plug and spray” solutions



Available Options:

WS-1000 Wet Station: Laurell designed and manufactured two-foot and four-foot options in fire-resistant CP7-D polypropylene

Rinse to Resistivity: Sensors detect when the rinse stage is complete and automatically advance the program to the drying stage, ensuring process repeatability and minimal use of valuable resources

Level Sensing: Monitor available chemistry and excess waste. Halt your process and set alerts to ensure safe operation

Leak Detection: The most dependable sensor technology available—an industry standard light tree with audible and visual alarms

Heated Process Chemistry: Heating available at the point-of-use or via recirculation-type heat exchangers

Teflon® Housings: Semiconductor grade Teflon® with **zero porosity** prevents “memory” effects and has the widest possible chemical resistance

Teflon® is a registered trademark of E.I. du Pont de Nemours & Co.



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